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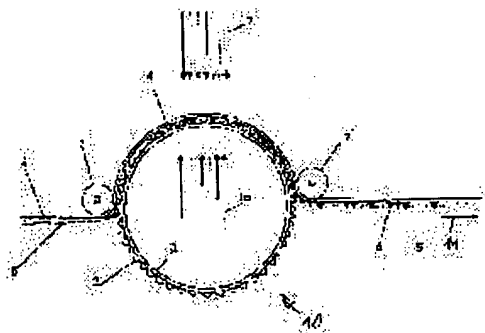
(54) METHOD AND APPARATUS FOR MAKING SURFACE STRUCTURE, ESPECIALLY  
 HOLOGRAM SURFACE STRUCTURE ON BASE MATERIAL

(57)Abstract:

PROBLEM TO BE SOLVED: To facilitate the preparation of a hologram surface structure on a base material by a method in which a radiation curable substance, especially a radiation curable monomer, is applied on the base material, an embossed pattern is formed in the coating film, and the pattern is cured by modulated irradiation beams.

SOLUTION: Foil or a film 4 coated with a radiation curable liquid monomer 5 is led to guide rollers 7, 7' and transferred along the surface of a rotary cylinder 10 in which surface structure 2, for example hologram surface structure, is formed on the outer surface of a cylinder surface 3. While the foil 4 is being contacted with the surface structure 2, an embossed pattern, namely the embossed pattern of the surface structure 2, is formed on the monomer coating film 5 of the foil 4.

Subsequently, only a prescribed area of the embossed pattern is modulated by irradiation beams 1a, 1b emitted from the outside and inside of the rotary cylinder 10. In this way, the monomer on the foil 4 is cured to obtain the foil 4 with the cured monomer 6.



## LEGAL STATUS

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